

United States Patent and Trademark Office



UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450

'.U. BOX 1430	
Mexandria, Virginia	22313-1450
vww.uspto.gov	

APPLICATION NO.	F.	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/783,035	02/15/2001		Katsuhide Manabe	Katsuhide Manabe PM 276665 6867 F99-156-USDIV	
21254	7590	09/07/2004	EXAMINER		INER
MCGINN & GIBB, PLLC 8321 OLD COURTHOUSE ROAD SUITE 200 VIENNA, VA 22182-3817			NGUYEN, THANH T		
			ART UNIT	PAPER NUMBER	
			2813		

DATE MAILED: 09/07/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

₹	Application No.	Applicant(s)
	09/783,035	MANABE ET AL.
Office Action Summary	Examiner	Art Unit
	Thanh T. Nguyen	2813
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply tf NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE!	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).
Status		· }
Responsive to communication(s) filed on <u>28 O</u> This action is FINAL . 2b) ☐ This Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro	J-773 /
Disposition of Claims		į
4) □ Claim(s) 18,19 and 22-26 is/are pending in the 4a) Of the above claim(s) 18 and 19 is/are with 5) □ Claim(s) is/are allowed. 6) □ Claim(s) 22-26 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/o	drawn from consideration.	
Application Papers		:
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomplicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Examine	epted or b) objected to by the liderawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		:
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage
Attachment(s)		:
1) ☐ Notice of References Cited (PTO-892) 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) ☑ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 10/28/03.	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal F 6) Other:	

Art Unit: 2813

DETAILED ACTION

Response to Arguments

Applicant's arguments filed 10/28/03 have been fully considered but they are not persuasive.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 22-26 are stand rejected under 35 U.S.C. 102(b) as being anticipated by Nakamura et al. (U.S. Patent No. 5,578,839) as previously applied.

Referring to figures 1-10, Nakamura et al. teaches a method for producing a lightemitting semiconductor device of a group III nitride compound, comprising:

Forming an N-layer of an N-type conduction (16, see figure 1, col. 5, lines 14-24), the N-layer comprising gallium nitride (16, It will be Gallium nitride when y=1),

Forming an emission layer of group III nitride compound semiconductor (18, see fig. 1, col. 5, lines 7-13) satisfying the formula, $Al_{x1}Ga_{y1}In_{1-x1-y1}N$, where 0=<x1=<1, 0=<y1=<1, 0=<x1+y1=<1, on the N-layer (18), Noted that when x1=0 then the formula will be $Ga_{y1}In_{1-y1}N$ which will be the same as formula of layer 18.

Forming a P-layer of P-type conduction (20, see col. 5, lines 25-32), on the emission layer (18), said p-layer comprising aluminum gallium nitride satisfying the formula Al_{x2}Ga_{1-x2}N,

Art Unit: 2813

where 0 < x2 < 1. Noted that when x2=0.5 then the formula will be $Al_{0.5}Ga_{0.5}N$ which will be the same as formula of layer 20.

Forming a contact layer of P-type conduction (34), on the P-layer, the contact layer comprising gallium nitride (see claim 19, col. 11, lines 44-47).

Doping Si into the N-layer and Mg into the P-layer (see col. 10, lines 38-67), so that a potential barrier of a valence band of the N-layer is lower than a potential barrier of a conduction band of the P-layer during conduction. It is held, absent evidence to the contrary that doping the N-type and P-type of dopant into the layer would facilitate the potential barrier of a valence band of the N-layer is lower than a potential barrier of a conduction band of the P-layer during conduction. See In re Best, 195 USPQ 428 (CCPA 1977) and In re Fitzgerald, 205 USPQ 594 (CCPA 1980).

Regarding to claim 23, the emission layer is doped with acceptor and donor impurities (18, see fig. 1, col. 5, lines 7-13).

Regarding to claim 24, the contact layer of P-type conductivity (34) is formed between the P-type layer (20) and an electrode (26, see fig. 11).

Regarding to claim 25, forming an electrode (26) contacting the contact layer (34, see fig. 11).

Response to Arguments

Applicant's arguments filed 10/28/03 have been fully considered but they are not persuasive.

The 112 rejection has been withdrawn.

Art Unit: 2813

Applicant contends that Nakamura doesn't disclose forming a layer made of n-GaN, an emission layer made of AlGaInN and a layer made of p-AlGaN. In response to applicant argument that In response to applicant's argument that the references fail to show certain features of applicant's invention, it is noted that the features upon which applicant relies (i.e., emission layer made of AlGaInN and a layer made of p-AlGaN) are not recited in the rejected claim(s). Although the claims are interpreted in light of the specification, limitations from the specification are not read into the claims. See In re Van Geuns, 988 F.2d 1181, 26 USPQ2d 1057 (Fed. Cir. 1993). Applicant claimed only forming an emission layer of group III nitride compound semiconductor satisfying the formula, $Al_{x1}Ga_{y1}In_{1-x1-y1}N$, where 0=<x1=<1, 0=<y1=<1, 0=<x1+y1 =<1, on the N-layer, Forming a P-layer of P-type conduction, on the emission layer, said p-layer comprising aluminum gallium nitride satisfying the formula Al_{x2}Ga_{1-x2}N, where 0<x2 <1. Therefore examiner reject the claims as: forming an emission layer of group III nitride compound semiconductor (18, see fig. 1, col. 5, lines 7-13) satisfying the formula, Al_{x1}Ga_{v1}In_{1-x1}. v_1N , where 0= $\langle x_1 = \langle 1, 0 = \langle y_1 = \langle 1, 0 = \langle x_1 + y_1 = \langle 1, 0 | x_1 \rangle$, on the N-layer (18), Noted that when $x_1 = \langle 1, 0 | x_1 \rangle$ then the formula will be Ga_{vl}In_{1-vl}N which will be the same as formula of layer 18. Forming a Player of P-type conduction (20, see col. 5, lines 25-32), on the emission layer (18), said p-layer comprising aluminum gallium nitride satisfying the formula $Al_{x2}Ga_{1-x2}N$, where $0 \le x \le 1$. Noted that when x2=0.5 then the formula will be Al_{0.5}Ga_{0.5}N which will be the same as formula of layer 20.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

Art Unit: 2813

Page 5

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanh Nguyen whose telephone number is (571) 272-1695, or by Email via address Thanh.Nguyen@uspto.gov. The examiner can normally be reached on Monday-Thursday from 6:00AM to 3:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached on (571) 272-1702. The fax phone number for this Group is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (703) 308-0956 (See MPEP 203.08).

THANKT WGUYEN
PRIMARY EXAMINER